

IN THE SPECIFICATION:

Please replace paragraph [0038] with the following amended paragraph:

[0038] Disposed between the polishing head assembly 154 and the polishing station 132 is polishing article, such as a web of polishing material 252. The web of polishing material 252 may have a smooth surface, a textured surface, or a combination of smooth and textured surfaces. For example, the web of polishing material may have a textured portion such as a center portion of the web or have a textured perimeter portion, while the remaining surface of the web is smooth. An example of a web of polishing material is described in co-pending Patent Application Serial No. 10/159,183, filed on May 31, 2003, ~~[Atty. Docket No. 6289/CMP/CMP/RKK]~~ which is incorporated herein by reference to the extent not inconsistent with the disclosure and claimed aspects herein.

Please replace paragraph [0044] with the following amended paragraph:

[0044] An example of such polishing material retention system is disclosed in United States Patent Application No. 09/258,036 6,491,570, ~~filed February 25, 1999 issued December 10, 2002~~, [[by]] of Sommer et al., which is hereby incorporated by reference. The reader should note that other types of devices might be utilized to fix the polishing material 252 to the platen 230, for example, adhesives, bonding, electrostatic chucks, mechanical clamps and other retention mechanisms.